L Number	Hits	Search Text	DB	Time stamp
2 Number	551236		USPAT;	2001/11/30 16:40
2	331230	photosensitive or photo-sensitive or	US-PGPUB;	2001, 11, 00 100
		(senstive near (photo or light or	EPO; JPO;	
		radiation or energy))	DERWENT;	
		radiation of emergy,	IBM TDB	
3	231522	carbon adj dioxide or co2 or "co.sub.2"	USPAT;	2001/11/30 15:51
	202024		US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM TDB	
4	1499642	polymer or polymeric or fluoropolymer or	USPAT;	2001/11/30 15:52
		monomer	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM TDB	0001/11/20 15 54
1	182		USPAT;	2001/11/30 15:54
		DESIMONE-JOSEPH-Min. DESIMONE-J-Min.	US-PGPUB;	
		DESIMONE-JOSEPHin.	EPO; JPO;	
		CARBONELL-RUBEN-Gin. CARBONELL-Rin.	DERWENT; IBM TDB	
_	13	(KENDALL-JONATHAN-Lin.	USPAT;	2001/11/30 16:59
5	13	DESIMONE-JOSEPH-Min. DESIMONE-J-Min.	US-PGPUB;	2001/11/30 10:33
i		DESIMONE GOSETH W .IN. BESIMONE G W .IN.	EPO; JPO;	
		CARBONELL-RUBEN-Gin. CARBONELL-Rin.	DERWENT;	
		CARBONELL-R-Gin. DESIMONE-J-Min.) and	IBM TDB	
		(resist or photoresist or photo-resist or		
		photosensitive or photo-sensitive or		
		(senstive near (photo or light or		
		radiation or energy))) and (carbon adj	i	
		dioxide or co2 or "co.sub.2") and (polymer		
		or polymeric or fluoropolymer or monomer)		
6	42	•	USPAT;	2001/11/30 16:42
		photosensitive or photo-sensitive or	US-PGPUB;	
		(senstive near (photo or light or	EPO; JPO;	
		radiation or energy))) with (carbon adj	DERWENT;	
		dioxide or co2 or "co.sub.2") with (polymer or polymeric or fluoropolymer or	IBM TDB \	
		monomer)		
8	166		USPAT;	2001/11/30 16:14
	100	photosensitive or photo-sensitive or	US-PGPUB;	2002, 22, 00
		(senstive near (photo or light or	EPO; JPO;	
		radiation or energy))) same (carbon adj	DERWENT;	
		dioxide or co2 or "co.sub.2") same	IBM TDB	
		(polymer or polymeric or fluoropolymer or		
		monomer)) not (((resist or photoresist or		·
		photo-resist or photosensitive or		
		photo-sensitive or (senstive near (photo		
		or light or radiation or energy))) with	1	
		(carbon adj dioxide or co2 or "co.sub.2")		;
		with (polymer or polymeric or fluoropolymer or monomer)) or	İ	1
1		((KENDALL-JONATHAN-Lin.	1	
		DESIMONE-JOSEPH-Min. DESIMONE-J-Min.		i
		DESIMONE-JOSEPHin.		
		CARBONELL-RUBEN-Gin. CARBONELL-Rin.		
		CARBONELL-R-Gin. DESIMONE-J-Min.) and		
1		(resist or photoresist or photo-resist or		
		photosensitive or photo-sensitive or		
		(senstive near (photo or light or		
		radiation or energy))) and (carbon adj	1	
1		dioxide or co2 or "co.sub.2") and (polymer	1	
		or polymeric or fluoropolymer or		
		monomer)))	USPAT;	2001/11/30 16:43
9	247	(resist or photoresist or photo-resist or photosensitive or photo-sensitive or	US-PGPUB;	2001/11/30 10.43
	1	(senstive near (photo or light or	EPO; JPO;	
		radiation or energy))) with (plasma with	DERWENT;	
	1	polymeriz\$5 or ppms!)	IBM TDB	
L	L	I POST TO TO PROMISE TO THE PROMISE		

			,	
10	1	((resist or photoresist or photo-resist or	USPAT;	2001/11/30 16:33
		photosensitive or photo-sensitive or (senstive near (photo or light or	US-PGPUB; EPO; JPO;	
		radiation or energy))) with (plasma with	DERWENT;	
		polymeriz\$5 or ppms!)) same (carbon adj	IBM TDB	
		dioxide or co2 or "co.sub.2")		
11	107	(photosensitive or photo-sensitive or	USPAT;	2001/11/30 16:35
		<pre>(sensitive near (photo or radiation or light or energy))) with (plasma with</pre>	US-PGPUB; EPO; JPO;	
		polymeriz\$5 or ppms!)	DERWENT;	
		polimoral or primery	IBM TDB	
12	16	, · · · <u>-</u>	USPAT;	2001/11/30 16:35
		(sensitive near (photo or radiation or	US-PGPUB; EPO; JPO;	
		light or energy))) with (plasma with polymeriz\$5 or ppms!)) and (carbon adj	DERWENT;	
		dioxide or co2 or "co.sub.2")	IBM TDB	
13	609228	resist or photoresist or photo-resist or	USPAT;	2001/11/30 16:41
		photosensitive or photo-sensitive or	US-PGPUB;	
		(sensitive near (photo or light or radiation or energy))	EPO; JPO; DERWENT;	
		radiation of energy//	IBM TDB	
15	5	((resist or photoresist or photo-resist or	USPAT;	2001/11/30 16:42
		photosensitive or photo-sensitive or	US-PGPUB;	
		(sensitive near (photo or light or radiation or energy))) with (carbon adj	EPO; JPO; DERWENT;	
		dioxide or co2 or "co.sub.2") with	IBM TDB	
		(polymer or polymeric or fluoropolymer or		
		monomer)) not ((resist or photoresist or		
		photo-resist or photosensitive or		
		photo-sensitive or (senstive near (photo or light or radiation or energy))) with		
		(carbon adj dioxide or co2 or "co.sub.2")		
:		with (polymer or polymeric or		
		fluoropolymer or monomer))	поръщ	2001/11/20 16.44
16	253	(resist or photoresist or photo-resist or photosensitive or photo-sensitive or	USPAT; US-PGPUB;	2001/11/30 16:44
		(sensitive near (photo or light or	EPO; JPO;	
		radiation or energy))) with (plasma with	DERWENT;	
	_	polymeriz\$5 or ppms!)	IBM TDB	2001/11/20 16:44
18	0	((photosensitive or photo-sensitive or (sensitive near (photo or radiation or	USPAT; US-PGPUB;	2001/11/30 16:44
		light or energy))) with (plasma with	EPO; JPO;	
		polymeriz\$5 or ppms!)) with develop\$4 with	DERWENT;	
		(carbon adj dioxide or co2 or "co.sub.2")	IBM TDB	2001 /11 /20 16.47
19	719	((carbon adj dioxide or co2 or "co.sub.2") with (polymer or polymeric or	USPAT; US-PGPUB;	2001/11/30 16:47
		fluoropolymer or monomer)) same (light or	EPO; JPO;	
		radiation or energy or expos\$3 or	DERWENT;	
		irradiat\$5)	IBM TDB	2001/11/20 16:40
21	365	((carbon adj dioxide or co2 or "co.sub.2") with (polymer or polymeric or	USPAT; US-PGPUB;	2001/11/30 16:48
		fluoropolymer or monomer)) with (light or	EPO; JPO;	
		radiation or energy or expos\$3 or	DERWENT;	
20	2-	irradiat\$5)	IBM TDB	2001/11/30 17:00
20	31	((carbon adj dioxide or co2 or "co.sub.2") with (polymer or polymeric or	USPAT; US-PGPUB;	2001/11/30 17:00
		fluoropolymer or monomer)) same (light or	EPO; JPO;	
		radiation or energy or expos\$3 or	DERWENT;	
		irradiat\$5) same (imagewise or patternwise	IBM TDB	
		or mask or photo-mask or pattern\$3 or photomask or reticle)		
22	485	(carbon adj dioxide or co2 or "co.sub.2")	USPAT;	2001/11/30 16:55
		with (polymer or polymeric or	US-PGPUB;	
		fluoropolymer or monomer) with (coat\$3 or	EPO; JPO; DERWENT;	
		deposit\$5 or form\$3 or appl\$4) with (layer or film or coating)	IBM TDB	
24	27	1	USPAT;	2001/11/30 17:02
		near3 (polymer or polymeric or	US-PGPUB;	
		fluoropolymer or monomer) near3 (coat\$3 or	EPO; JPO;	
		deposit\$5 or form\$3 or appl\$4) near3 (layer or film or coating)	DERWENT; IBM TDB	
L		Trayer or rring or coucing,	1	

25	2	((carbon adj dioxide or co2 or "co.sub.2")	USPAT;	2001/11/30 16:59
		near3 (polymer or polymeric or	US-PGPUB;	
		fluoropolymer or monomer) near3 (coat\$3 or	EPO; JPO;	i
	į	deposit\$5 or form\$3 or appl\$4) near3	DERWENT;	!
		(layer or film or coating)) and (resist or	IBM TDB	
		photoresist or photo-resist or		
		photosensitive or photo-sensitive or		
		(sensitive near (photo or light or		1
		radiation or energy)))	ĺ	
26	4		USPAT;	2001/11/30 17:01
	1	near3 (polymer or polymeric or	US-PGPUB;	
		fluoropolymer or monomer) near3 (coat\$3 or	EPO; JPO;	
		deposit\$5 or form\$3 or appl\$4) near3	DERWENT;	
		(layer or film or coating)) and ((light	IBM TDB	
		or radiation or energy or expos\$3 or		
		irradiat\$5) same (imagewise or patternwise		
		or mask or photo-mask or pattern\$3 or		
		photomask or reticle))		
27	5		USPAT;	2001/11/30 17:02
	1	or ("5665527") or ("6045877")).PN.	US-PGPUB	2224 /24 /22 47 22
28	5		USPAT;	2001/11/30 17:08
		("5739223") or ("5665527") or	US-PGPUB	
İ		("6045877")).PN.) and ((resist or		1
ĺ	į	photoresist or photo-resist or		
	1	photosensitive or photo-sensitive or		ĺ
		(sensitive near (photo or light or		
		radiation or energy))) or (carbon adj		
	1	dioxide or co2 or "co.sub.2") or (polymer		
		or polymeric or fluoropolymer or monomer))		2001/11/20 17:04
30	4		USPAT;	2001/11/30 17:04
		("5739223") or ("5665527") or	US-PGPUB	
		("6045877")).PN.) and ((resist or		
		photoresist or photo-resist or		
		photosensitive or photo-sensitive or		
		(sensitive near (photo or light or		
		radiation or energy))) and (carbon adj		
		dioxide or co2 or "co.sub.2") and (polymer		
	i	or polymeric or fluoropolymer or monomer))		